

Table I–12 to Subpart I of Part 98–Default Emission Factors (1–U_{ij}) for Gas Utilization Rates (U_{ij}) and By-Product Formation Rates (B_{ijk}) for Semiconductor Manufacturing for use with the Stack Test Method (300 mm and 450 mm Wafer Sizes)

All Processes	Process Gas i											C ₄ F ₈ O	
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	CH ₃ F	C ₃ F ₈	C ₄ F ₈	NF ₃	NF ₃ Remote	SF ₆	C ₄ F ₆		C ₅ F ₈
1-U _i	0.65	0.80	0.42	0.21	0.33	0.20	0.18	0.20	0.018	0.32	0.15	0.10	NA
BCF ₄	NA	0.21	0.095	0.049	0.045	0.21	0.045	0.040	0.075	0.040	0.059	0.11	NA
BC ₂ F ₆	0.079	NA	0.064	0.052	0.00087	0.18	0.031	0.045	NA	0.044	0.074	0.083	NA
BC ₄ F ₆	NA	NA	0.00010	NA	NA	NA	0.018	NA	NA	NA	NA	NA	NA
BC ₄ F ₈	0.00063	NA	0.00080	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA
BC ₃ F ₈	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	0.00012	NA
BCH ₂ F ₂	NA	NA	0.0036	NA	0.0023	NA	0.0015	0.00086	NA	0.000029	0.000030	NA	NA
BCH ₃ F	0.0080	NA	0.0080	0.0080	NA	0.00073	NA	0.0080	NA	NA	NA	NA	NA
BCHF ₃	0.011	NA	NA	0.050	0.0057	0.012	0.027	0.025	NA	0.0037	0.019	0.0069	NA

Notes: NA = Not applicable; i.e., there are no applicable emission factor measurements for this gas. This does not necessarily imply that a particular gas is not used in or emitted from a particular process sub-type or process type.